

| L Number | Hits | Search Text | DB | Time stamp |
|----------|--------|---|---|------------------|
| 1 | 483 | sputtering same (inline in-line) | USPAT | 2003/03/11 08:22 |
| 2 | 79 | sputtering same (inline in-line) same (conventional well-known (well adj known)) | USPAT | 2003/03/11 08:51 |
| 3 | 3 | spf-530h | USPAT | 2003/03/11 08:51 |
| 4 | 0 | spf-530h same (inline in-line) | USPAT | 2003/03/11 09:18 |
| 5 | 72 | (crystal near size) same (sputtering) | USPAT | 2003/03/11 09:18 |
| - | 2 | jp-08225936-\$.did. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2001/08/15 16:07 |
| - | 13553 | jp-08225936-\$.did.MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2001/08/15 16:14 |
| - | 13553 | jp-08225936-\$.did.MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2001/08/15 16:15 |
| - | 13551 | MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 08:49 |
| - | 4 | ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank)) and (substrate support) and (helium "He") | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/05 13:08 |
| - | 25 | (MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/05 13:06 |
| - | 22 | (photomask adj blank) and (substrate support) and (helium "He") | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2002/03/28 15:17 |
| - | 603 | (photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2001/08/16 11:00 |
| - | 63 | ((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2002/03/28 15:16 |
| - | 3548 | (antireflective ARC) same (chromium adj nitride Cr?N?) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2001/08/16 11:22 |
| - | 744 | sputtering same (("ar" argon) and (helium "He")) | USPAT; US-PGPUB | 2001/08/16 11:57 |
| - | 60 | ((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber)) not ((photomask adj blank) and (substrate support) and (helium "He")) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2001/08/16 12:38 |
| - | 263296 | (430/5 430/322 430/320 428/\$ 427/\$).CCLS. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2001/08/16 12:41 |
| - | 139 | ((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?\$) AND (SPUTTER SPUTTERING SPUTTERED) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2001/08/16 12:49 |
| - | 260869 | HE?\$(HEADLEY-J-L) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2001/08/16 12:48 |
| - | 702 | ((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (SPUTTER SPUTTERING SPUTTERED) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2001/08/16 12:49 |

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| - | 442 | ((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?\$5) AND (SPUTTER SPUTTERING SPUTTERED) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2001/08/16 12:52 |
| - | 449 | ((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?\$3) AND (SPUTTER SPUTTERING SPUTTERED) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2001/08/16 12:58 |
| - | 80 | ((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2002/03/28 15:16 |
| - | 73 | ((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED)) NOT ((photomask adj blank) and (substrate support) and (helium "He")) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2001/08/16 13:07 |
| - | 92 | ((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/05 13:05 |
| - | 78 | ((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/05 13:05 |
| - | 30 | (photomask adj blank) and (substrate support) and (helium "He") | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/05 13:05 |
| - | 1 | ep-1022614-\$.did. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2002/03/28 15:25 |
| - | 1 | ("5830332").PN. | USPAT | 2002/03/28 15:26 |
| - | 16 | ("3840451" "4417946" "4486286" "4529475" "4551216" "4620898" "4624736" "4684436" "4822466" "4851097" "4913789" "4973345" "5045165" "5073241" "5122249" "5429730").PN. | USPAT | 2002/03/28 15:26 |
| - | 1 | ("4720442").PN. | USPAT | 2002/03/28 15:36 |
| - | 5 | ("4363846" "4374912" "4497878" "4530891" "4563407").PN. | USPAT | 2002/03/28 15:43 |
| - | 5 | ("4363846" "4374912" "4497878" "4530891" "4563407").PN. | USPAT | 2002/03/28 15:51 |
| - | 13 | 4720442.URPN. | USPAT | 2002/03/28 15:52 |
| - | 37 | ((((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED)) ((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber)) ((photomask adj blank) and (substrate support) and (helium "He"))) and @pd>=20010731 | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2002/03/28 16:19 |
| - | 331 | (sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2") | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2002/03/28 16:20 |
| - | 13 | ((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblank) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/05 13:05 |
| - | 626 | ("He" Helium) same (chromium) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2002/03/28 16:35 |

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| - | 28 | ((("He" Helium) same (chromium)) and (blank photomask adj blank photoblack)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/05 13:05 |
| - | 3 | gb-2325473-\$.did. or ep-605814-\$.did. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/05 12:12 |
| - | 93 | ((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/05 13:05 |
| - | 118 | ((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/05 13:06 |
| - | 32 | ((("He" Helium) same (chromium)) and (blank photomask adj blank photoblack)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/05 13:06 |
| - | 16 | ((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblack)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/05 13:07 |
| - | 47 | (photomask adj blank) and (substrate support) and (helium "He") | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/05 13:07 |
| - | 8 | ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank)) and (substrate support) and (helium "He") | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/05 13:07 |
| - | 31 | ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/05 13:07 |
| - | 26299 | tensile adj stress | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/05 13:09 |
| - | 9 | ((gb-2325473-\$.did. or ep-605814-\$.did.) ((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber)) (((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED)) (((("He" Helium) same (chromium)) and (blank photomask adj blank photoblack)) (((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblack)) ((photomask adj blank) and (substrate support) and (helium "He")) (((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank)) and (substrate support) and (helium "He")) ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank))) and (tensile adj stress)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/05 13:46 |

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| - | 56 | ((gb-2325473-\$.did. or ep-605814-\$.did.) (((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber)) (((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED)) ((("He" Helium) same (chromium)) and (blank photomask adj blank photoblack)) (((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblack)) ((photomask adj blank) and (substrate support) and (helium "He")) (((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank) and (substrate support) and (helium "He")) ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank))) and (deposition adj rate) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/05 13:46 |
| - | 51 | ((gb-2325473-\$.did. or ep-605814-\$.did.) (((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber)) (((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED)) ((("He" Helium) same (chromium)) and (blank photomask adj blank photoblack)) (((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblack)) ((photomask adj blank) and (substrate support) and (helium "He")) (((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank) and (substrate support) and (helium "He")) ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank))) and (deposition adj rate)) not (((gb-2325473-\$.did. or ep-605814-\$.did.) (((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber)) (((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED)) ((("He" Helium) same (chromium)) and (blank photomask adj blank photoblack)) (((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblack)) ((photomask adj blank) and (substrate support) and (helium "He")) (((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank) and (substrate support) and (helium "He")) ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank))) and (tensile adj stress)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 10:33 |
| - | 0 | 605814.URPN. | USPAT | 2003/03/06 10:04 |
| - | 0 | 605814.URPN. | USPAT | 2003/03/06 10:05 |

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| - | 4 | ((("4663183") or ("4728529"))).PN. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 10:21 |
| - | 252 | flatness adj degree | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 10:22 |
| - | 4975 | (blank photomask mask) and (thin adj film) and (substrate support) and (helium "He") | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 12:47 |
| - | 3 | ((blank photomask mask) and (thin adj film) and (substrate support) and (helium "He")) and (flatness adj degree) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 10:23 |
| - | 154 | ((blank photomask mask) and (thin adj film) and (substrate support) and (helium "He")) and (tensile near stress) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 10:27 |
| - | 571552 | (transition near metal) (chromium "Cr") | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 10:32 |
| - | 60 | ((((blank photomask mask) and (thin adj film) and (substrate support) and (helium "He")) and (tensile near stress)) and ((transition near metal) (chromium "Cr")) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 10:33 |

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| - | 52 | (((gb-2325473-\$.did. or ep-605814-\$.did.) (((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber)) (((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPATTERED)) (((He" Helium) same (chromium)) and (blank photomask adj blank photoblack)) (((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblack)) ((photomask adj blank) and (substrate support) and (helium "He")) (((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank)) and (substrate support) and (helium "He")) ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank))) and (deposition adj rate)) not (((gb-2325473-\$.did. or ep-605814-\$.did.) (((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber)) (((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPATTERED)) (((He" Helium) same (chromium)) and (blank photomask adj blank photoblack)) (((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblack)) ((photomask adj blank) and (substrate support) and (helium "He")) (((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank)) and (substrate support) and (helium "He")) ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank))) and (tensile adj stress)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 10:35 |
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| - | 60 | (((blank photomask mask) and (thin adj film) and (substrate support) and (helium "He")) and (tensile near stress)) and ((transition near metal) (chromium "Cr"))) not (((("4663183") or ("4728529")).PN.) ((blank photomask mask) and (thin adj film) and (substrate support) and (helium "He")) and (flatness adj degree)) (((gb-2325473-\$.did. or ep-605814-\$.did.) ((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber)) (((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED)) (((("He" Helium) same (chromium)) and (blank photomask adj blank photoblack)) (((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblack)) ((photomask adj blank) and (substrate support) and (helium "He")) (((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank)) and (substrate support) and (helium "He")) ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank))) and (deposition adj rate)) not (((gb-2325473-\$.did. or ep-605814-\$.did.) ((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber)) (((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED)) (((("He" Helium) same (chromium)) and (blank photomask adj blank photoblack)) (((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblack)) ((photomask adj blank) and (substrate support) and (helium "He")) (((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank)) and (substrate support) and (helium "He")) ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (photomask adj blank))) and (tensile adj stress))) (tensile adj stress) (warp warping flatness) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 12:23 |
| - | 150556 | | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 12:23 |
| - | 6812 | ((tensile adj stress) (warp warping flatness)) and (sputtering) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 12:24 |
| - | 457 | (((tensile adj stress) (warp warping flatness)) and (sputtering)) and ((blank photomask mask) and (thin adj film) and (substrate support) and (helium "He")) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 12:25 |
| - | 432 | (((tensile adj stress) (warp warping flatness)) and (sputtering)) and ((blank photomask mask) and (thin adj film) and (substrate support) and (helium "He"))) and (metal (transition near metal) chromium chrome "Cr") | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 12:48 |

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| - | 5873 | 430/5.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 12:48 |
| - | 16 | 430/5.ccls. and (((((tensile adj stress) (warp warping flatness)) and (sputtering)) and ((blank photomask mask) and (thin adj film) and (substrate support) and (helium "He")))) and (metal (transition near metal) chromium chrome "Cr")) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 15:34 |
| - | 41 | (dc.m/c. adj power) near source | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 15:54 |
| - | 19876 | power adj density | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 15:55 |
| - | 28 | (power adj density) same (sputter adj target) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 16:40 |
| - | 0 | (dc.m/c. adj bias adj potential) same (graphite near target) same ("W" watts watt) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 16:50 |
| - | 408 | (dc.u/c. adj power adj source) same ("W" watts watt) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/06 16:57 |
| - | 15071 | MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 09:16 |
| - | 1239 | ROSASCO ROSASCO-S ROSASCO-STEPHAN ROSASCO-STEPHEN ROSASCO-STEPHEN-D ROSASCO-STEVE ROSASCO-STEVEN | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 08:59 |
| - | 18 | (MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (ROSASCO ROSASCO-S ROSASCO-STEPHAN ROSASCO-STEPHEN ROSASCO-STEPHEN-D ROSASCO-STEVE ROSASCO-STEVEN) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 08:59 |
| - | 390 | (MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (helium "He") | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 09:17 |
| - | 591 | (MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (helium "He" (inert adj gas)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 09:17 |
| - | 191 | ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (helium "He")) and (metal) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 09:18 |
| - | 66 | ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (helium "He")) and (metal) and target | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 09:18 |
| - | 4 | ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO) and (helium "He")) and (metal) and target) and (vacuum near chamber) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 10:22 |
| - | 16095 | sccm | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 10:25 |

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|---|-------|---|---|------------------|
| - | 7 | (direct adj current adj sputter) same (vacuum inline in-line chamber power) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 10:27 |
| - | 20 | (direct adj current adj sputter) and (vacuum inline in-line chamber power) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 11:55 |
| - | 13 | ((direct adj current adj sputter) and (vacuum inline in-line chamber power)) not ((direct adj current adj sputter) same (vacuum inline in-line chamber power)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 11:55 |
| - | 249 | ((tensile adj stress) (flatness near degree)) same (helium He (inert)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 12:46 |
| - | 19876 | (power adj density) same (power) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 12:47 |
| - | 12 | ((power adj density) same (power)) same (graphite adj target) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 15:47 |
| - | 2 | (cm2) same (graphite adj target) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 13:04 |
| - | 75 | (cm2 cm inch in2 centimeter meter) same (graphite adj target) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 13:05 |
| - | 2 | jp-11012730-\$.did. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 15:08 |
| - | 1298 | (silicon adj wafer) same transparent | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 15:12 |
| - | 3 | spf-530H | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 16:16 |
| - | 325 | (sputtering adj power) same (rate) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/03/10 16:19 |
| - | 249 | (sputtering adj power) same (rate) | USPAT | 2003/03/11 08:20 |